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## P.E.S. College of Engineering, Mandya - 571 401

(An Autonomous Institution affiliated to VTU, Belagavi)

**Fifth Semester, B.E. - Electronics and Communication Engineering**

**Semester End Examination; Feb. - 2021**

**Digital CMOS VLSI Design**

*Time: 3 hrs*

*Max. Marks: 100*

*Note: Answer FIVE full questions, selecting ONE full question from each unit.*

### UNIT - I

- 1 a. Explain the formation of depletion region and inversion layer in  $n$  - channel enhancement type MOSFET with neat figure and band diagram. 8
- b. A polysilicon gate  $n$  - channel MOS transistor with substrate doping density  $2 \times 10^8 \text{ cm}^{-3}$ , polysilicon gate doping density  $3 \times 10^{15} \text{ cm}^{-3}$ , gate oxide thickness  $500 \text{ \AA}$ , oxide interface charge  $6.4 \times 10^{-9} \text{ C/cm}^2$ ,  $\epsilon_{si} = 11.7 \epsilon_0$ ,  $n_i = 1.45 \times 10^{10} \text{ cm}^{-3}$ . Calculate the threshold voltage  $V_{TO}$  at  $V_{SB} = 0$ . 8
- c. Discuss the concept of substrate bias effect and its effect on drain current. 4
- 2 a. Discuss the concept of full scaling of MOSFET and its effect on device characteristics (any four). 8
- b. An  $n$  - channel MOS process with following parameters:  
Substrate doping density  $N_A = 10^{16} \text{ cm}^{-3}$ , polysilicon gate doping density  $N_D(\text{gate}) = 2 \times 10^{20} \text{ cm}^{-3}$ ,  $C_{ox} = 7.03 \times 10^{-8} \text{ F/cm}^2$ ,  $V_{TO} = 0.855 \text{ V}$  junction depth at source and drain diffusion region  $x_j = 1.0 \text{ \mu m}$ ,  $L = 1 \text{ \mu m}$ ,  $\epsilon_{si} = 11.7 \epsilon_0$ ,  $\phi_F(\text{Substrate}) = 0.35 \text{ V}$ . Calculate; 7
- i) Zero drain bias  $x_{ds}$  and  $x_{dD}$                       ii) Threshold voltage shift due to short channel effect
- c. Explain the oxide related capacitance of MOSFET. 5

### UNIT - II

- 3 a. Define the term noise margin and noise immunity. Illustrate the effect of noise on the circuit reliability. 8
- b. Consider depletion load inverter circuit with the following parameters:  
 $V_{DD} = 5 \text{ V}$ ,  $V_{To, driver} = 1.0 \text{ V}$ ,  $V_{To, load} = -3.0 \text{ V}$ ,  $K'_{n driver} = K'_{n load} = 50 \text{ \mu A/V}^2$ ,  
 $\left(\frac{W}{L}\right)_{driver} = 2$ ,  $\left(\frac{W}{L}\right)_{load} = \frac{1}{3}$ ,  $\gamma = 0.4 \text{ V}^{\frac{1}{2}}$ ,  $\phi_F = -0.3 \text{ V}$  6  
Calculate;    i)  $V_{OH}$                       ii)  $V_{OL}$
- c. Draw the circuit of CMOS inverter and explain its operation with voltage transfer characteristics. 6
- 4 a. Discuss the calculation of propagation delay time for high to low output transition  $\tau_{PHL}$  along related waveforms and equations. 8

- b. Explain the calculation of interconnect delay using Elmore delay method. 8
- c. Write the importance of power delay product PDP in CMOS process. 4

### UNIT - III

- 5 a. Write the CMOS NOR2 gate and its inverter equivalent. Obtain the equation for its switching threshold voltage. 6
- b. Design the CMOS circuit for the following: 6
- i)  $F = \overline{(C + D)E + AB}$                       ii)  $Z = A \oplus B$
- c. Explain the operation of CMOS transmission gate for different bias conditions and operating regions. 8
- 6 a. Discuss the small signal analysis of two inverter bistable circuit along with related equation and diagrams. 8
- b. Write the circuit of CMOS negative (falling) edge triggered master slave D flip flop and explain its working. 8
- c. Write the Gate-level schematic and AOI based implementation of the clocked NOR-based SR latch circuit. 4

### UNIT - IV

- 7 a. Analyze the pass transistor circuit for logic '0' transfer and calculate the fall time. 8
- b. Explain the voltage bootstrapping with relevant equations. 8
- c. Write note on charge leakage from the soft node. 4
- 8 a. Explain the operation of rationed and ratioless synchronous dynamic logic along with circuit diagram. 8
- b. Discuss the working of NP-Domino logic. 6
- c. Explain the general circuit structure and clock signals of zipper CMOS circuits. 6

### UNIT - V

- 9 a. Explain the working of conventional BiCMOS inverter circuit with active base pull-down. 7
- b. Write the circuit diagram for the following: 6
- i) BiCMOS NOR2 gate
- ii) BiCMOS NAND2 gate
- c. Analyze the BJT operating in saturation mode using Ebers-Moll equivalent circuit diagram. 7
- 10 a. Discuss the different models for ESD testing. 8
- b. Explain the output circuit and  $L\left(\frac{di}{dt}\right)$  noise. 8
- c. Write note on H-tree clock distribution technique. 4